

Graduate Student Finalists Compete at 1993 MRS Fall Meeting

At the 1993 MRS Fall Meeting in Boston, 30 finalists will compete for the MRS Graduate Student Awards, to be presented on Wednesday evening, December 1, during ceremonies also honoring the 1993 Von Hippel, MRS Medalist, and Turnbull Lectureship recipients.

Graduate Student Award Finalists, all authors or co-authors of papers to be presented at the Fall Meeting, were selected on the basis of the quality and thoroughness of their research, the originality and independence of their contributions, and their promise for future achievement in materials research.

Graduate Student Award Finalists—1993 MRS Fall Meeting

Pushkar P. Apte, Stanford University, "Thermally Driven *In Situ* Removal of Native Oxide Using Anhydrous Hydrogen Fluoride (Symposium Ca)

Valarie I. Benezra, Naval Research Laboratory, "Selective Attachment of Synthetic DNA to Sam-Functionalized Surfaces" (Symposium S)

Thomas Boland, University of Washington, "Concerns and Complications in STM Imaging of Adsorbed Proteins and Biomolecules on Gold Surfaces" (Symposium U)

Y. Michael Cheng, Lehigh University, "Oriented Carbon Pair Defects Stabilized by Hydrogen in As-Grown GaAs Epitaxial Layers" (Symposium L)

Nigel Clarke, University of Sheffield, "Kinetics of Concentration Fluctuations and Spinodal Decomposition in Star/Star and Star/Linear Polymer Blends" (Symposium O)

J.F. Dorsten, University of Illinois-Urbana, "Changes in Near-Surface Electronic Structure of Organic Thiol-Passivated GaAs (100) Studied by Raman Spectroscopy" (Symposium Ca)

H. Edelman, University of Wisconsin, "The Effect of Local Variations in Microstructure on the Critical Current of (Bi,Pb)₂Sr₂Ca₂Cu₃O_x Tapes (Symposium H)

Ahmed R. El-Ghannam, University of Pennsylvania, "Bioactive Glass Template for the Synthesis of Bone-Like Tissue *In Vitro*" (Symposium T)

Steven G. Haupt, University of Texas-Austin, "Molecule/Superconductor Structures and Devices" (Symposium H)

Richard M. Jacobinas, University of California-Los Angeles, "Synthesis of

During special sessions beginning at 12 noon on Monday, November 29, the finalists will give brief talks explaining their research to a panel of judges who will select the award recipients. Among the judges will be organizers from the symposia in which the finalists are participating, members of the MRS Awards Committee, and other MRS representatives. MRS Fall Meeting participants are also invited to attend.

The following list identifies the finalists, their places of study, the titles of their papers, and the symposium in which each is participating.

High-Temperature Silicides Via Rapid Solid-State Metathesis" (Symposium F)

Peter Kofinas, Massachusetts Institute of Technology, "Shear-Induced Morphology of Semicrystalline Diblock and Triblock Copolymers" (Symposium E)

Michael P. Mallamaci, University of Minnesota, "In Situ TEM Crystallization of Anorthite Glass Films on α -Al₂O₃" (Symposium E)

Stuart A. Maloy, Los Alamos National Laboratory, "The Temperature and Strain Rate Dependence of the Flow Stress in MoSi₂ Single Crystals" (Symposium F)

Sining Mao, University of Maryland, "High-T_c Superconducting *p-n* Junctions" (Symposium H)

Amy J. Moll, University of California-Berkeley, Lawrence Berkeley Laboratory, "The Effects of Amorphous Layer Regrowth on Acceptor Activation in III-V Semiconductors" (Symposium A)

Jerry F. Moore Jr., SUNY-Stony Brook, "Deposition of Dielectric Thin Films from Condensed Layers of Reactants Excited by Ultraviolet and Soft X-Ray Radiation" (Symposium Y)

D.A. Muller, Cornell University, "Electronic Structure and Bonding at Interfaces between CVD Diamond and Silicon (Symposium U)

Christopher M. Rouleau, University of Florida, "Real-Time *In Situ* Monitoring of Defect Evolution at Widegap II-VI/GaAs Heterointerfaces During Epitaxial Growth (Symposium K/M)

Frank Stepniak, University of Minnesota, "Surface Etching of GaAs (100) and (110) with Chlorine and Bromine" (Symposium W)

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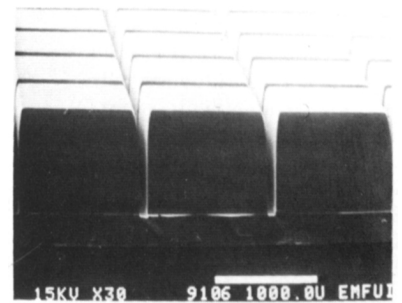


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John P. Sullivan, University of Pennsylvania "CoSi₂/Si(111) Interface Structure and its Influence on the Schottky Barrier" (Symposium D)

Britt A. Turkot, University of Illinois-Urbana, "Ion Damage Studies in GaAs/AlGaAs/GaAs Heterostructures" (Symposium A)

Glenn T. Visscher, Pennsylvania State University, "Poly(phenylcarbyne): A Polymer Precursor to Diamond-Like Carbon" (Symposium Q)

Ravi Viswanathan, University of California-Santa Barbara, "Visualizing the Hexatic to Crystalline Transition in L-B Films with AFM (Symposium U)

H. Weidner, University of Central Florida, "Energy Transfer Between Two Sites in Nd³⁺:KLiYF₆" (Symposium R)

Keith Whittingham, Cornell University, "Selective Area OMVPE Growth of GaInP on Patterned GaAs Substrates Using Semimetallic Amorphous Carbon Mask" (Symposium M)

Joyce Y. Wong, Massachusetts Institute of Technology, "Cell Interactions with

Fibronectin-Coated Electrically Conducting Polypyrrole Thin Films" (Symposium T)

Hang Xu, Harvard University, "C₆₀⁻ Induced Reconstruction on Ge(111) Surface" (Symposium G)

Taner Yildirim, University of Pennsylvania, "Phase Diagram of Na_xC₆₀ (0 < x < 3)" (Symposium G)

Chao-Yang Zhang, Massachusetts Institute of Technology, "Gravitational Compression of a Highly Swollen Lyotropic Liquid Crystal" (Symposium O)

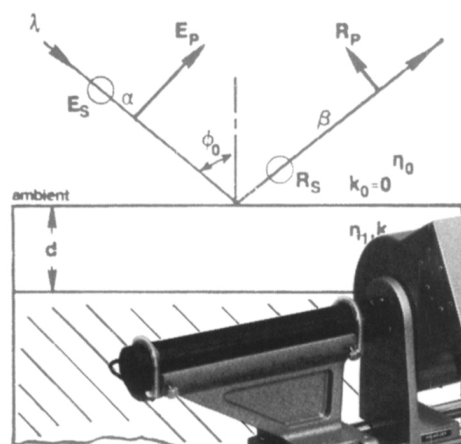
Jun Fei Zheng, University of California-Berkeley, "Atomic Scale Interface Structure of In_{0.2}Ga_{0.8}As/GaAs Strained Layers Studied by Cross-Sectional Scanning Tunneling Microscopy" (Symposium Cb)



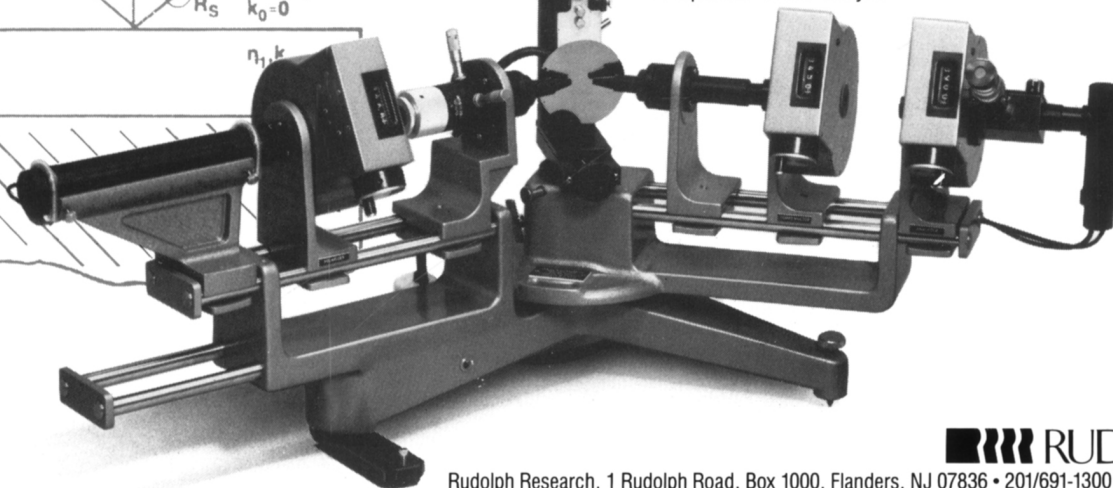
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MRS EXHIBIT

Boston Marriott Hotel Tuesday-Thursday, November 30 – December 2, 1993

As part of the 1993 Fall Meeting, a major exhibit will be held to display analytical and processing equipment closely paralleling the nature of the technical symposia. The exhibit will be in the Boston Marriott Hotel and a table-top display on the fourth floor of the Westin Hotel. The technical program has been arranged to allow meeting participants ample opportunity to visit the exhibit.

Exhibit Hours

Tuesday	noon - 7:00 p.m.
Reception.....	5:00 p.m. - 7:00 p.m.
Wednesday	9:30 a.m. - 5:00 p.m.
Thursday	9:30 a.m. - 2:00 p.m.

Coffee will be available during morning and afternoon breaks in the Exhibit area, Tuesday afternoon through Thursday morning.

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